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Recent Advances in Machine Learning and Applications

Guest Editor:

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Deadline for manuscript submissions:

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Message from the Guest Editor

To review recent advances in machine learning, this Special Issue on "Recent Advances in Machine Learning and Applications" will focus on publishing high-quality original research studies that address challenges in the broad area of optimization and artificial intelligence inprocess applications. Topics include but are not limited to the following:

- ML models and applications for predictive maintenance, quality control, and process optimization
- ML models and applications for smart manufacturing process monitoring and control
- ML models and application for intelligent manufacturing diagnostics, prognostics, and asset health management
- ML models and applications for scheduling and supply chain management
- ML models and applications for robotics and human–machine interaction
- ML algorithms and approaches to handling big data, data imbalance, uncertainty, data fusion, etc.











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Message from the Editor-in-Chief

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